

Notice of References Cited	Application/Control No. 10/598,143		Applicant(s)/Patent Under Reexamination BAUER ET AL.	
	Examiner David Ziskind		Art Unit 2818	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,847,448	12-1998	Val et al.	257/686
*	B	US-2004/0026007	02-2004	Hubert et al.	156/64
*	C	US-2002/0105789	08-2002	Chen et al.	361/767
*	D	US-7,060,526	06-2006	Farnworth et al.	438/106
*	E	US-2003/0038353	02-2003	Derderian, James M.	257/685
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Norland Materials Data Sheet, February 1998.			
	V	Choi et al., A Photocurable Poly(dimethylsiloxane) Chemistry Designed for Soft Lithographic Molding and Printing in the Nanometer Regime, J. AM.Chem. Soc., Vol. 125, pp. 4060-1, 2003			
	W				
	X				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.06(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.